

[METHOD OF FABRICATING POLYSILICON FILM]

Abstract

A method of fabricating polysilicon film is described. An amorphous silicon layer is formed on the substrate, an optical layer is formed on the amorphous silicon layer, wherein the optical has a first region having a first thickness and a second region having a second thickness, and the reflectivity of the first region for an excimer laser is higher than that of the second region. A laser annealing process is then performed to transform the amorphous silicon layer into a polysilicon film.